

162162

ABSTRACT

A wafer carrier cleaner which comprises a base having a first aperture and a second aperture. The wafer cleaner includes a first sprayer, and a second sprayer, with the first sprayer configured to direct a series of cleaning fluids about the exterior surface of a wafer carrier, and the second sprayer configured to direct a series of cleaning fluids about the interior surface of a wafer carrier. The expended fluids used to clean the exterior surface of the wafer carrier are directed through the first aperture and into a first fluidic circuit, and the expended fluids used to clean the interior surface of the wafer carrier are directed through the second aperture and into a second fluidic circuit. The provision of dedicated fluidic circuits for the exterior and interior cleaning fluids reduces cross contamination.



G00001